

**10/587194**  
**IAP11 Rec'd PCT/PTO 24 JUL 2006**

PATENT

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

**EXPRESS MAIL NO. EV827401168US**

Appl No. : To be assigned Confirmation No. N/A  
Applicant : Jean-Louis Stehle  
Filed : July 24, 2006  
Title : PROTECTED PATTERN MASK FOR REFLECTION LITHOGRAPHY IN  
THE EXTREME UV OR SOFT X-RAY RANGE  
TC/A.U. : To be assigned  
Examiner : To be assigned  
Docket No. : 58059/N75  
Customer No. : 23363

**PRELIMINARY AMENDMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Post Office Box 7068  
Pasadena, CA 91109-7068  
July 24, 2006

Commissioner:

Prior to examination, please amend the above-identified application as follows:

**Amendments to the Specification** begin on page 2 of this paper.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 3 of this paper.

**Remarks/Arguments** begin on page 7 of this paper.

**Appendix** an Abstract of the Disclosure, on a separate page, is attached following page 6 of this paper.